

## INFORMATION DISCLOSURE CITATION

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Applicant	Ogasawara et al.		
Filing Date	June 25, 2003	Prior Group:	2877

U.S. PATENT DOCUMENTS						
Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Dat If Appropriate
HP	5,315,123	5/1994	Itoh et al.	_____	_____	
HP	5,285,075	2/1994	Minamide et al.	_____	_____	
HP	5,136,169	8/4/92	Smith et al.	_____	_____	
HP	4,808,829	2/1989	Okumura et al.	_____	_____	
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HP	4,376,249	3/1983	Pfeiffer et al.	_____	_____	
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FOREIGN PATENT DOCUMENTS						
	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
			None			

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)	
HP	Goodberlet et al., "Spatial-Phase-Locked Electron-Beam Lithography with a Delay-Locked Loop," J. Vac. Sci. Technol. (1997), B15(6): 2293-97
HP	Smith et al., "A New Approach to High Fidelity E-Beam and Ion-Beam Lithography Based on an <i>in situ</i> Global-Fiducial Grid," J. Vac. Sci. Technol. (1991), B9(6):2992-95
HP	Smith et al., "Application of Moiré Techniques in Scanning-Electron-Beam Lithography and Microscopy," J. Vac. Sci. Technol. (1975), 12: 1262-65

Examiner	<i>HP</i>	Date Considered	11/8/04
*Examiner:	Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.		
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